Notice of Allowability	Application No.	Applicant(s)		
	10/760,995	LIU ET AL.		
	Examiner	Art Unit		
	Thanh T. Nguyen	2813		
The MAILING DATE of this communication appears on the cover sheet with the correspondence address All claims being allowable, PROSECUTION ON THE MERITS IS (OR REMAINS) CLOSED in this application. If not included herewith (or previously mailed), a Notice of Allowance (PTOL-85) or other appropriate communication will be mailed in due course. THIS NOTICE OF ALLOWABILITY IS NOT A GRANT OF PATENT RIGHTS. This application is subject to withdrawal from issue at the initiative of the Office or upon petition by the applicant. See 37 CFR 1.313 and MPEP 1308.				
1. This communication is responsive to <u>11/21/06</u> .				
2. The allowed claim(s) is/are 1-5, 8-23.				
<ul> <li>3. Acknowledgment is made of a claim for foreign priority unally All b) Some* c) None of the:</li> <li>1. Certified copies of the priority documents have</li> <li>2. Certified copies of the priority documents have</li> <li>3. Copies of the certified copies of the priority documents have</li> <li>International Bureau (PCT Rule 17.2(a)).</li> </ul>	been received. been received in Application No		ition from the	
* Certified copies not received:				
Applicant has THREE MONTHS FROM THE "MAILING DATE" of this communication to file a reply complying with the requirements noted below. Failure to timely comply will result in ABANDONMENT of this application.  THIS THREE-MONTH PERIOD IS NOT EXTENDABLE.				
4. A SUBSTITUTE OATH OR DECLARATION must be submit INFORMAL PATENT APPLICATION (PTO-152) which give	tted. Note the attached EXAMINER's reason(s) why the oath or declarate	S AMENDMENT or N tion is deficient.	OTICE OF	
5. CORRECTED DRAWINGS ( as "replacement sheets") must be submitted.				
(a) 🔲 including changes required by the Notice of Draftsperson's Patent Drawing Review ( PTO-948) attached				
1) 🗌 hereto or 2) 🔲 to Paper No./Mail Date				
(b) ☐ including changes required by the attached Examiner's Amendment / Comment or in the Office action of Paper No./Mail Date				
Identifying indicia such as the application number (see 37 CFR 1. each sheet. Replacement sheet(s) should be labeled as such in the	84(c)) should be written on the drawing he header according to 37 CFR 1.121(c	gs in the front (not the	back) of	
<ol> <li>DEPOSIT OF and/or INFORMATION about the deposit attached Examiner's comment regarding REQUIREMENT I</li> </ol>	sit of BIOLOGICAL MATERIAL m FOR THE DEPOSIT OF BIOLOGICA	nust be submitted. N AL MATERIAL.	Note the	
Attachment(s)  1. — Notice of References Cited (PTO-892)	5. ☐ Notice of Informal Pa	atent Application		
2. Notice of Draftperson's Patent Drawing Review (PTO-948)	6. Interview Summary			
Information Disclosure Statements (PTO/SB/08),     Paper No./Mail Date	7. Examiner's Amendm	Paper No./Mail Date  Examiner's Amendment/Comment		
Examiner's Comment Regarding Requirement for Deposit of Biological Material	8. ⊠ Examiner's Stateme 9. □ Other	nt of Reasons for Allo	wance	

## **REASONS FOR ALLOWANCE**

## The following is an examiner's statement of reasons for allowance:

Claims 1-5, 8-10 are allowed because none of the prior art alone or in combination teaches or suggests the particular subset of the process steps intermediary cleaning process is performed 1~3 minutes, and wherein the intermediary cleaning process further comprises the steps of: using O<sub>2</sub>, Cl<sub>2</sub> and SF<sub>6</sub> as a first cleaning gas for about 30 second, and using Cl<sub>2</sub>, and HBr as a second cleaning gas for about 50 seconds.

Claims 11-23 are allowed over the prior art because none of the prior art alone or in combination teaches or suggests the particular subset of the process steps in forming a capping layer with a bird's beak overlying the polysilicon layer, and etching each of the polysilicon layers in sequence in a plasma chamber using the overlying capping layer as an etch mask to form a floating gate on each of the floating gate dielectric layers, a polymer layer being deposited over the inner wall of the plasma chamber during the etching, wherein an intermediary cleaning process is performed in the plasma chamber between the etchings before the deposited polymer layer reaches such a degree as to induce lateral etching on the next polysilicon layer.

Any comments considered necessary by applicant must be submitted no later than the payment of the issue fee and, to avoid processing delays, should preferably accompany the issue fee. Such submissions should be clearly labeled "Comments on Statement of Reasons for Allowance."

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## **Conclusion**

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Thanh Nguyen whose telephone number is (571) 272-1695, or by Email via address Thanh.Nguyen@uspto.gov. The examiner can normally be reached on Monday-Thursday from 6:00AM to 3:30PM.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Carl Whitehead, Jr., can be reached on (571) 272-1702. The fax phone number for this Group is (571) 273-8300.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pairdirect.uspto.gov. Should you have questions on access to thy Private PAIR system, contact the Electronic Business center (EBC) at 866-217-9197 (toll-free).

Thanh Nguyen

Patent Examiner

Patent Examining Group 2800

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